# Monthly LabAdviser update: 3/5 2019

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| Updated Subject  | Contributor | Link to the updated pages |
| **IBE Etch**Al2O3 etch with Ti mask in Ionfab300+. Selectivities. | **Sezer Köse @fotonik** | [/IBE%E2%81%84IBSD\_Ionfab\_300/IBE\_Au\_etch#Al2O3\_using\_Ti\_mask\_etching\_with\_the\_.22Au\_acceptance\_recipe.22](http://labadviser.nanolab.dtu.dk/index.php/Specific_Process_Knowledge/Etch/IBE%E2%81%84IBSD_Ionfab_300/IBE_Au_etch#Al2O3_using_Ti_mask_etching_with_the_.22Au_acceptance_recipe.22) |
| **ALD1**Deposition and characterization of HfO2 made in ALD1 | **Evgeniy Shkondin @Nanolab** | [Thin\_film\_deposition/ALD\_Picosun\_R200/HfO2\_deposition\_using\_ALD\_new\_page](http://labadviser.nanolab.dtu.dk/index.php/Specific_Process_Knowledge/Thin_film_deposition/ALD_Picosun_R200/HfO2_deposition_using_ALD_new_page) |
| **DRIE Pegasus Si etching**Deep Si nano etching – The DREM process. | **Bingdong Chang @Nanolab** | [Etch/DRIE-Pegasus/Etch\_silicon\_nanostructures](http://labadviser.nanolab.dtu.dk/index.php/Specific_Process_Knowledge/Etch/DRIE-Pegasus/Etch_silicon_nanostructures) |
| **Aluminium deposition in Temescal**New page on Al-deposition in Temescal | **Evgeniy Shkondin @Nanolab** | [Deposition\_of\_Aluminium/Al\_Ebeam\_evaporation\_in\_Temescal](http://labadviser.nanolab.dtu.dk/index.php/Specific_Process_Knowledge/Thin_film_deposition/Deposition_of_Aluminium/Al_Ebeam_evaporation_in_Temescal) |

# Equipment Manuals updated in LabManager (since 13th of Marts):

As an approved user on a piece of equipment you have to make sure you have read and understood the latest version of the manual before using the equipment.

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|  |  **Manual for Al Anneal furnace (C4)** |
|  | **Manual for Nitride etch: H3PO4** |
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